

**A PROCESS FOR DEVICE FABRICATION USING PROJECTION
LITHOGRAPHY AND AN APPARATUS THEREFOR**

Abstract

The invention is directed to a method and apparatus of projection
5 lithography in which the contrast introduced into a radiation sensitive material
caused by the proximity effect is effectively removed in a single exposure. Patterned
radiation is transmitted through a lens system with at least one lens and a back focal
plane filter. The back focal plane filter has at least two apertures, an image aperture
and a proximity effect correction aperture. Patterned radiation is transmitted through
10 the image aperture and introduces the desired image into the energy sensitive resist
material. A portion of the inverse pattern radiation is transmitted through the
proximity effect correction aperture and onto the energy sensitive resist material to
effectively remove the contrast therein caused by the proximity effect.

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